(54) Title: GENERALIZATION OF THE PHOTO PROCESS WINDOW AND ITS APPLICATION TO OPC TEST PATTERN DESIGN
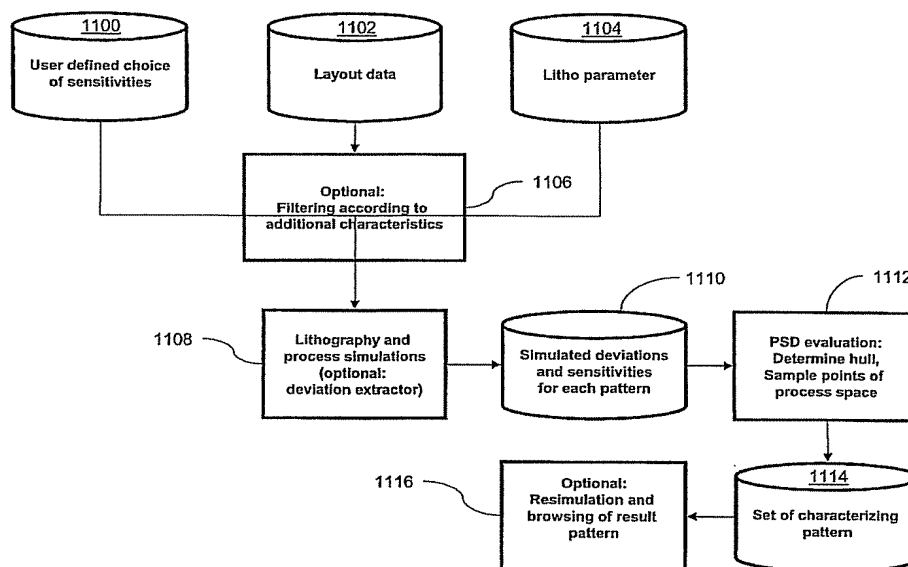
(57) Abstract: A method comprises the steps of: (a) simulating on a processor a fabrication of a plurality of layout patterns by a lithographic process; (b) determining sensitivities of the layout patterns to a plurality of parameters based on the simulation; (c) using the sensitivities to calculate deviations of the patterns across a range of each respective one of the parameters; and (d) selecting ones of the patterns having maximum or near-maximum deviations to be used as test patterns.

WO 2005/081910 A2